ABSTRACT

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A polymer comprising recurring units containing silicon and recurring units having a substituent group of formula (1) is novel wherein A^1 is a divalent group selected from furandiyl, tetrahydrofurandiyl and oxanorbornanediyl, R^1 and R^2 are selected from monovalent C_1 - C_{10} hydrocarbon groups, or R^1 and R^2 taken together may form an aliphatic hydrocarbon ring with the carbon atom, and R^3 is hydrogen or a monovalent C_1 - C_{10} hydrocarbon group which may contain a hetero atom. The polymer is useful as a base resin to formulate a resist composition which is sensitive to high-energy radiation, and has excellent sensitivity and resolution at a wavelength of less than 300 nm as well as satisfactory oxygen plasma etching resistance.